## **Supplementary Materials**

## First-principles analysis of photocurrent in monolayer $\alpha$ -selenium *p-n* junctions optoelectronic device

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**Fig. S1** Band structure of the monolayer (ML)  $\alpha$ -selenium with (a) *p*- and (b) *n*-doping (doping concentration is 8.21×10<sup>14</sup> cm<sup>-2</sup>).



Fig. S2 Band structure and density of state of the ML  $\alpha$ -selenium with different stress (a) -2%, (b) -1%, (c) 1%, and (d) 2%.





**Fig. S3** Strain-dependent photoresponsivity of the ML  $\alpha$ -selenium *p-n* junction optoelectronic device along ARM directions under different photon energies and linearly polarized direction (a) -2%, (g) -1%, (d) 1%, and (j) 2%. Strain-dependent photoresponsivity value of the ML  $\alpha$ -selenium *p-n* junction optoelectronic device under different photon energy as a function of linearly polarized direction along the ARM direction direction (b)(c) -2%, (h)(i) -1%, (e)(f) 1%, and (k)(l) 2%.



Fig. S4 Local device density of states (PDOS) of the ML selenium *p*-*n* junctions optoelectronic device under different gate voltage  $V_{g}$ .